

IN THE CLAIMS:

Please CANCEL claims 1, 4, 6 and 8-13 without prejudice to or disclaimer of the recited subject matter.

Please AMEND claims 2, 3, 5, 7 and 14, as follows. For the Examiner's convenience, all claims currently pending in this application have been reproduced below:

1. (Cancelled)

2. (Currently Amended) An exposure apparatus according to Claim ~~1~~ 14, wherein said processing system further performs sensitivity correction of said first photodetector relative to an illuminance on a plane corresponding to a surface of the photosensitive object on the basis of the change of transmittance of at least an optical element between a position where light divided to said first photodetector and a photosensitive object.

3. (Currently Amended) An exposure apparatus according to Claim ~~1~~ 14, further comprising a stage movable in a direction orthogonal to an optical axis of said illumination optical system, on which the original is placed, and a second photodetector disposed near the photosensitive object, wherein said second photodetector detects the exposure light passing through a light transmitting portion of said stage placed at a position different from that of a portion where the pattern is positioned.

4. (Cancelled)

5. (Currently Amended) An exposure apparatus according to Claim ~~1~~ 14, wherein said light source includes one of a KrF excimer laser, an ArF excimer laser, and an F2 laser.

6. (Cancelled)

7. (Currently Amended) An apparatus according to Claim ~~1~~ 14, further comprising a second photodetector, disposed near the photosensitive object, having a light receiving surface positioned at the same height as a surface of the photosensitive object, wherein said processing system further performs sensitivity corrections of said first photodetector and said second photodetector on the basis of the changes in transmittance of at least an optical element between the position where light divided to said first photodetector and said second photodetector.

8-13. (Cancelled)

14. (Currently Amended) An exposure apparatus comprising:
a light source of a pulsed laser;
an illumination optical system illuminating an original on which a pattern is formed by exposure light emitted from said light source;

a projection optical system projecting the pattern to a photosensitive object;

a first photodetector disposed in a portion for receiving light from an optical path between said light source and a portion where the original is placed, said first photodetector being used for monitoring an emission light amount from said light source; and

a processing system performing sensitivity correction of said first photodetector relative to information of a pulse energy of the light source, an oscillation frequency of the light source, a time of irradiating a pulsed laser light to said illumination optical system in said oscillation frequency, and a time when the pulsed laser light is not irradiated to said illumination optical system and is longer than a pulse period of said oscillation frequency.

15. (Cancelled)

16. (Cancelled)

17. (Previously Presented) An exposure apparatus according to Claim 14, wherein said processing system performs sensitivity correction on the basis of at least one of information regarding an illumination extent of said illumination optical system, and information regarding transmittance of the original.